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PATENT
Attorney Docket No.: SAM-0483
Customer No.: 29344

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Jae-eun Park, *et al.* Examiner: Not Yet Assigned
Serial No.: 10/782,094 Group Art Unit: 2813
Filing Date: February 19, 2004
Title: METHOD FOR FORMING SILICON DIOXIDE FILM USING SILOXANE

CERTIFICATE OF MAILING UNDER 37 C.F.R. § 1.8

I hereby certify that this correspondence is being deposited with the United States Post Office as First Class Mail on the date indicated below in an envelope addressed to Mail Stop Amendment, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

7-7-04

Date

Vanessa Marakas

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

TRANSMITTAL LETTER

Sir:

Enclosed herewith for filing in the above-identified patent application please find the following listed items:

1. Supplemental Information Disclosure Statement;
2. Forms PTO-1449 and copies of cited references AB-AF and AL-AR; and
3. Return Postcard.

In connection with the foregoing matter, please charge any additional fees which may be due, or credit any overpayment, to Deposit Account Number 50-1798. A duplicate copy of this letter is provided for this purpose.

Respectfully submitted,

Date: July 7, 2004
Mills & Onello, LLP
Eleven Beacon Street, Suite 605
Boston, Massachusetts 02108
Telephone: (617) 994-4900
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Anthony P. Onello, Jr.
Registration Number 38,572
Attorney for Applicants



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Alexandria, VA 22313-1450

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Sir:

This Information Disclosure Statement is submitted:

- ☐ under 37 CFR 1.129(a), or
(First/Second submission after Final Rejection)
- ☒ under 37 CFR 1.97(b), or
(Within three months of filing national application other than a CPA under §1.53(d); or within three months of date of entry of the national stage in international application; or before mailing date of first Office Action on the merits; or before mailing date of first Office Action after filing RCE under §1.114, whichever occurs last)
- ☐ under 37 CFR 1.97(c) together with either:
- ☐ a Statement under 37 CFR 1.97(e), as checked below, or
- ☐ the \$180.00 fee under 37 CFR 1.17(p), or
(After the 37 CFR 1.97(b) time period, but before final action or notice of allowance, or other action which closes prosecution, whichever occurs first)
- ☐ under 37 CFR 1.97(d) together with:
- ☐ a Statement under 37 CFR 1.97(e), as checked below, and
- ☐ the \$180.00 fee set forth in 37 CFR 1.17(p).
(Filed after final action or notice of allowance, whichever occurs first, but before payment of the issue fee)

Applicant(s): Jae-eun Park, *et al.*
Serial No.: 10/782,094

Statement Under 37 C.F.R. 1.97(e)

- ☒ Each item of information contained in this Information Disclosure Statement was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this Information Disclosure Statement.
- ☐ No item of information contained in this Information Disclosure Statement was cited in a communication from a foreign patent office in a counterpart foreign application or, to the knowledge of the undersigned, after making reasonable inquiry, was known to any individual designated in 37 CFR 1.56(c) more than three months prior to the filing of this Information Disclosure Statement.

Enclosed herewith is form PTO-1449:

- ☒ Copies of cited references are enclosed.
- ☐ Copies of cited references are enclosed except those entered in prior application, U.S. Serial No. _____, and references that are not required to be submitted under 37 CFR 1.98.
- ☐ The listed references were cited in a counterpart foreign application.

Concise Explanation Requirement (non-English references):

- ☒ The "concise explanation" requirement under 36 CFR 1.98(a)(3)(i) for references AL, AO and AP is satisfied by:
- ☐ the explanation provided on the attached sheet.
- ☐ the explanation provided in the Specification.
- ☒ submission of the enclosed Search Report in related European application 03253968.6.
- ☒ abstract.

It is requested the information disclosed herein be made of record in this application.

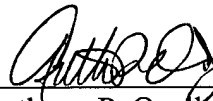
Applicant(s): Jae-eun Park, *et al.*
Serial No.: 10/782,094

Method of payment:

- ☐ Enclosed is a check in the amount of _____.
- ☐ Please charge Deposit Account of 50-1798 in the amount of _____.
- ☐ Two duplicate copies of this Statement are enclosed.
- ☒ Please charge any deficiency in fees and credit any overpayment to Deposit Account No. 50-1798.

Respectfully submitted,

Date: July 7, 2004
Mills & Onello, LLP
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Anthony P. Onello, Jr.
Registration Number 38,572
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Supp. Form PTO-1449 INFORMATION DISCLOSURE CITATION IN AN APPLICATION <i>(Use several sheets if necessary)</i>				Docket Number (Optional) SAM-0483		Application Number 10/782,094		
				Applicant Jae-eun Park, et al.				
				Filing Date 02/19/04		Group Art Unit 2813		
U. S. Patent Documents								
EXAMINER INITIALS		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
	AA							
	AB	5,470,800	11-28-95	Muroyama	437	238	03-26-93	
	AC	6,037,275	03-14-00	Wu, et al.	438	780	08-27-98	
	AD	6,270,572	08-07-01	Kim, et al.	117	93	08-09-99	
	AE	2002/0001974	01-03-02	Chan	438	785	06-20-01	
	AF	6,391,803	05-21-02	Kim, et al.	438	787	06-20-01	
	AG							
	AH							
	AI							
	AJ							
	AK							
FOREIGN PATENT DOCUMENTS								
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation YES NO	
	AL	06132276	05-13-94	Japan	H01L	21/312		X
	AM	1 096 042	05-02-01	Europe	C30B	25/02		
	AN	1 003 210	05-24-00	Europe	H01L	21/316		
	AO	10189582	07-21-98	Japan	H01L	21/316		X
	AP	2001002990	01-09-01	Japan	C09D	183/04		X
	AQ	1 139 399	10-04-01	Europe	H01L	21/306		
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)								
	AR	Klaus, J.W., et al., "Atomic layer controlled growth of SiO ₂ films using binary reaction sequence chemistry," American Institute of Physics, 1997, Pages 1092-1094						
	AS							
	AT							
EXAMINER					DATE CONSIDERED			
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy with next communication to applicant.								